

Epitaxial Growth and Characterization of Sr-Doped Lanthanum Titanate Thin Films

陳星宇、宋皇輝

E-mail: 9708121@mail.dyu.edu.tw

ABSTRACT

In this study, Sr-doped LaTiO_3 ($\text{Sr}_x\text{La}_{1-x}\text{TiO}_3$, SLTO, $x \leq 0.6$) thin films were grown on the $\text{Si}(100)$ and $\text{LaTiO}_3(100)$ substrates by the off-axis rf magnetron co-sputtering system. In the experiments, we expect some La^{3+} ions were replaced by Sr^{2+} ions in the samples, and introduced the hole carriers. The in-situ grown specimens show electrical conduction, and the temperature dependence of resistivity and Hall coefficients were measured to study the transport properties. The temperature dependence of the resistance metallic and deviate from free electron gas model obviously. The transport behavior can be attributed to the electron-phonon interaction in the system. The Hall measurements show the films are p-type for $x < 0.5$ and switch to n-type at $x > 0.5$. In addition, near the transition edge, the samples $x = 0.57$ and $x = 0.60$ change from p-type to n-type below the room temperature.

Keywords : $\text{Sr}_x\text{La}_{1-x}\text{TiO}_3$; electron-phonon interaction ; transport ; Hall coefficient

Table of Contents

封面內頁 簽名頁 授權書	iii	中文摘要	
. iv		英文摘要 v	
. vi		誌謝 vii	
. ix		目錄 xii	
.		圖目錄	
第一章 緒論 1.1前言	1	1.2研究背景	
. 1.1.3文獻回顧	3	1.4論文架構	
. 8		第二章 實驗量測原理 2.1電阻率量測	9
. 10		2.2霍爾量測原理	13
. 14		2.3 X-ray繞射原理	24
. 16		2.4膜後量測原理	28
. 17		第三章 樣品製備與量測 3.1樣品製備	21
. 17		3.1.1靶材製備	21
. 22		3.1.2實驗流程	21
. 24		3.1.3實驗流程敘述	22
. 24		3.2定性與定量量測	24
. 26		3.2.1 X-ray繞射分析儀	25
. 29		3.2.2掃描式電子顯微鏡(SEM)	25
. 29		3.2.3微區成分分析儀(EDS)	26
. 33		3.3電性量測	28
. 51		3.4霍爾量測	28
. 55		第四章 結果與討論 4.1薄膜樣品之成長參數與結構、成分分析	33
. 58		4.2薄膜樣品之傳輸特性	41
		4.3薄膜Hall量測之探討	51
		第五章 結論	55
		參考文獻	58

REFERENCES

- [1]李志晃, " 摻釷 SrTiO_3 之傳輸特性研究 ", 大葉大學碩士論文, 2006 [2]A.Ohtomo, D.A.Muller, J. L. Grazul, and H. Y. Hwang, Appl. Phys. Lett. 80, 21 (2002) [3]B. Vilquin, T. Kanki, T. Yanagida, H. Tanaka, T. Kawai, Applied Surface Science 244, 494-497 (2005) [4] B. Vilquin, T. Kanki, T. Yanagida, H. Tanaka, T. Kawai, Solid State Communication 136, 328-332 (2005) [5]J.E. Sunstrom, S.M. Kauzlarich, P. Klavins, Chem. Mater. 4, 346 (1992) [6]Y. Okada, T. Arima, and Y. Tokura, Phys. Rev. B 48, 9677 (1993) [7]C. C. Hays, J.-S. Zhou, J. T. Markert, and J. B. Goodenough, Phys. Rev. B 60, 10367 (1999) [8]Y. Tokura, Y. Taguchi, Y. Okada, Y. Fujishima, and T. Arima, Phys. Lett. 70, 2126 (1992) [9]J. Li, F. B. Wang, P. Wang, M. J. Zhang, H. Y. Tian, and D. N. Zheng, Phys. Rev. B 75, 195109 (2007) [10]吳文斌、黃迪靖 ; 科學研究 " 強電子關聯材料的軌域物理 " 2004年8月 [11]Ralf Moos, and Karl Heinz Hardtl, J. Appl. Phys. 80, 393 (1996) [12]V. N. Bogomolov, E. K. Kudinov, and Y. A. Firsov, Sov. Phys. Solid State 9, 2502 (1968)